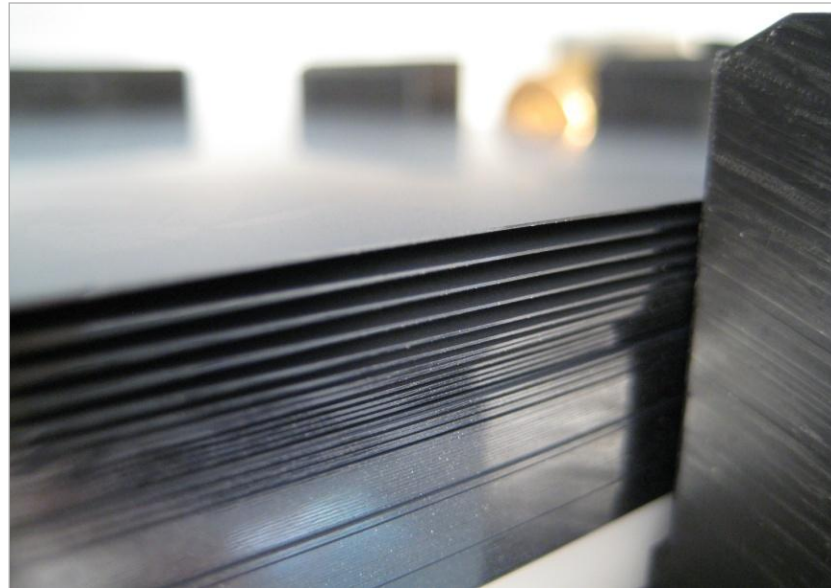


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# Separation process of thin crystalline silicon-wafer with compressed air

## 1. Workshop „Handling and Automation of Solar Wafer and Cells“

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Stuttgart, 13th January 2011

Alexander Ehm

# Outline

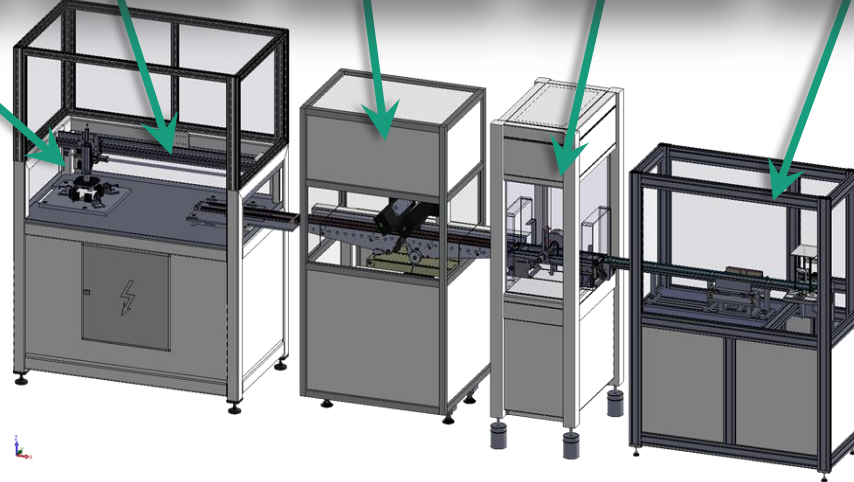
1. Motivation
2. Requirements wafer separation
3. Pick-and-place Process
4. Analysis and optimization of the separation process
5. Summary and Outlook

# 1. Motivation

Pre-Separation Pick-and-place Micro-Crack Flipping Carrier Loading

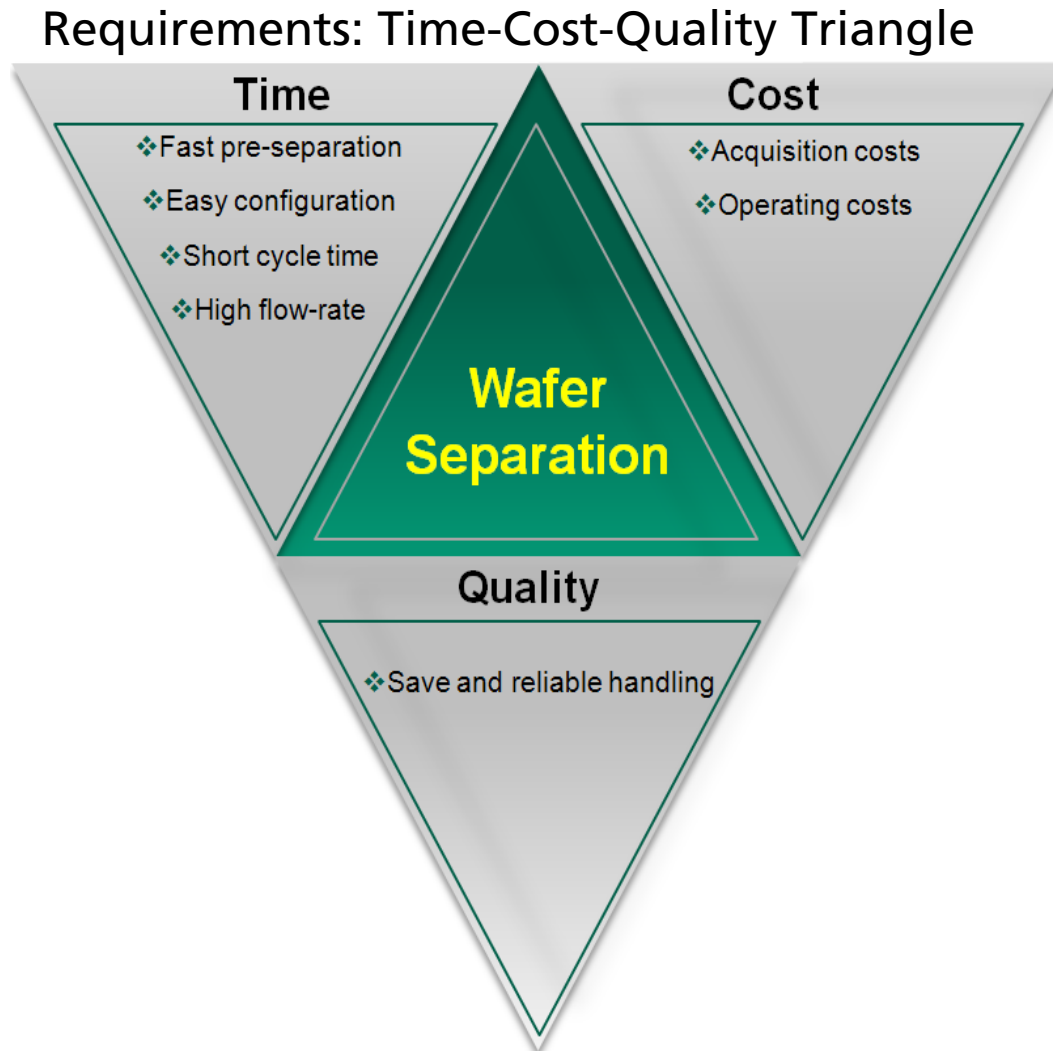


**Results:**  
**Final Test Runs**  
**„High Sol“**

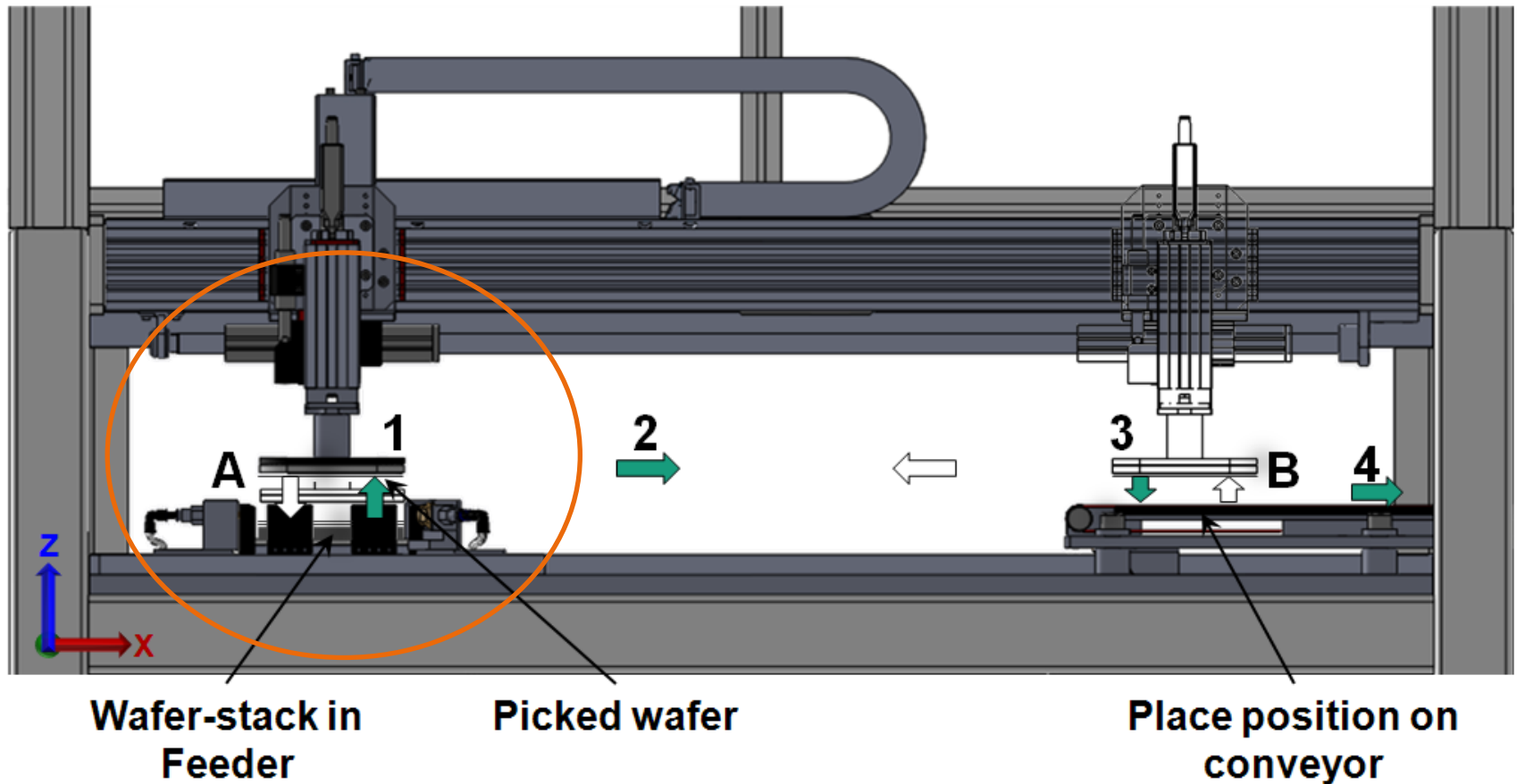


<i>Station</i>	<i>Pre-Separation</i>	<i>Pick-and-Place</i>	<i>Micro-Crack</i>	<i>Flipping</i>	<i>Carrier Loading</i>
Rel. Breakage Rate [%]	51%	26%	0%	17%	6%

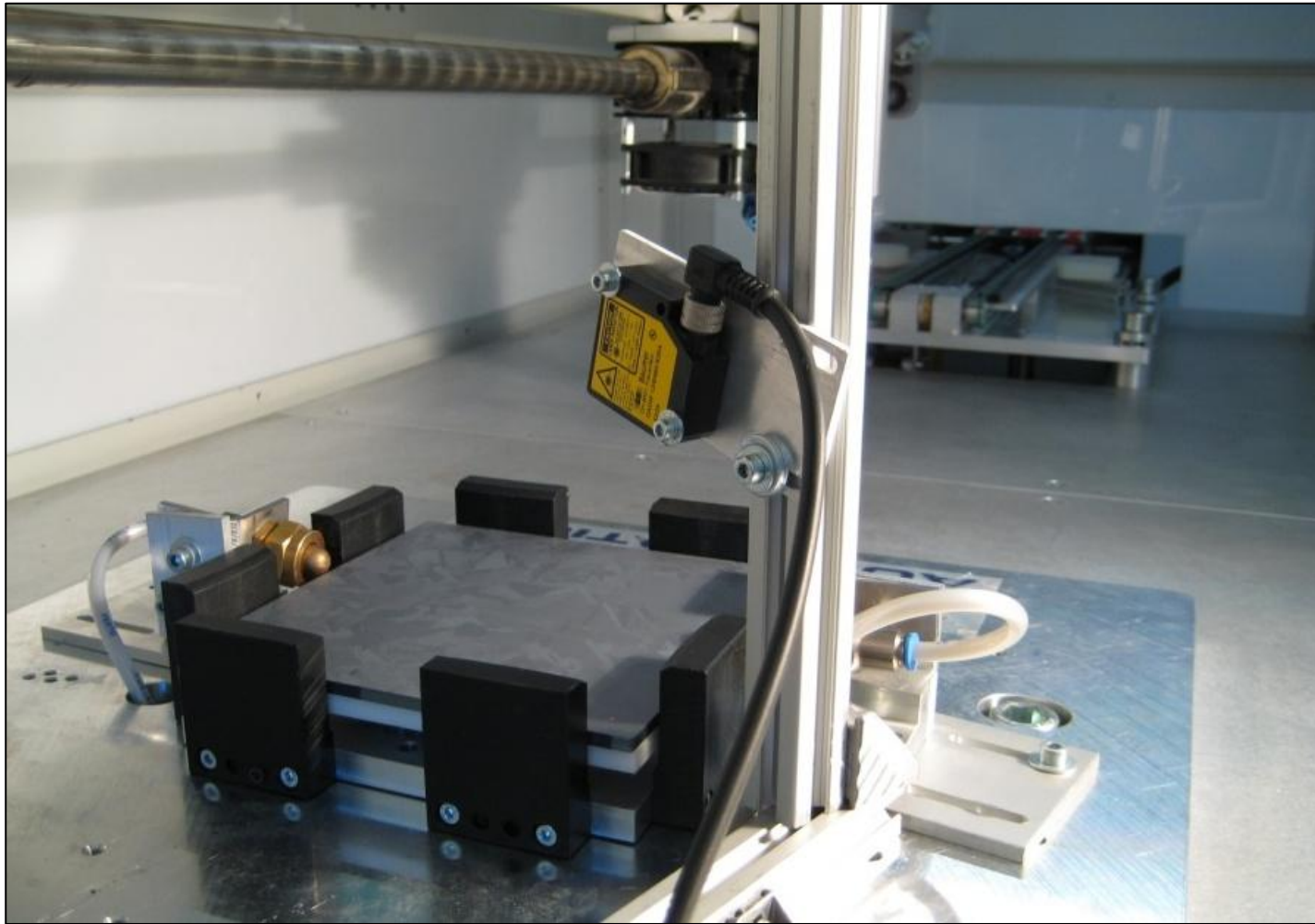
## 2. Requirements wafer separation



### 3. Pick-and-place Process

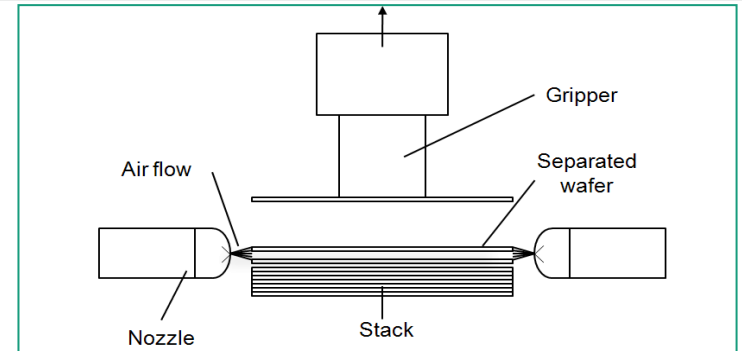
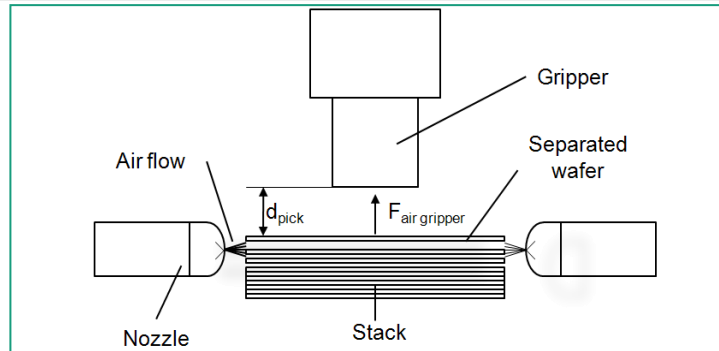


# Initial state of Feeder



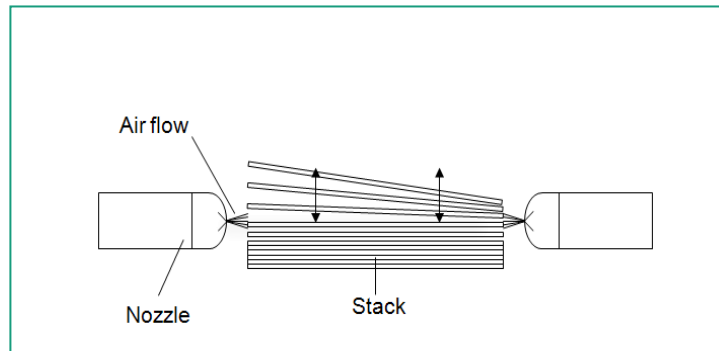
# 4. Analysis and optimization of the separation process

## 1. Optimal Separation and Picking

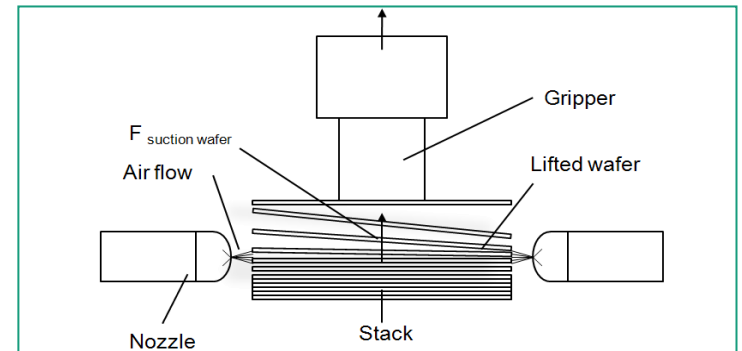


## 2. Real Separation and Picking

### 1<sup>st</sup> challenge:



### 2<sup>nd</sup> challenge:



**Main Challenges:**

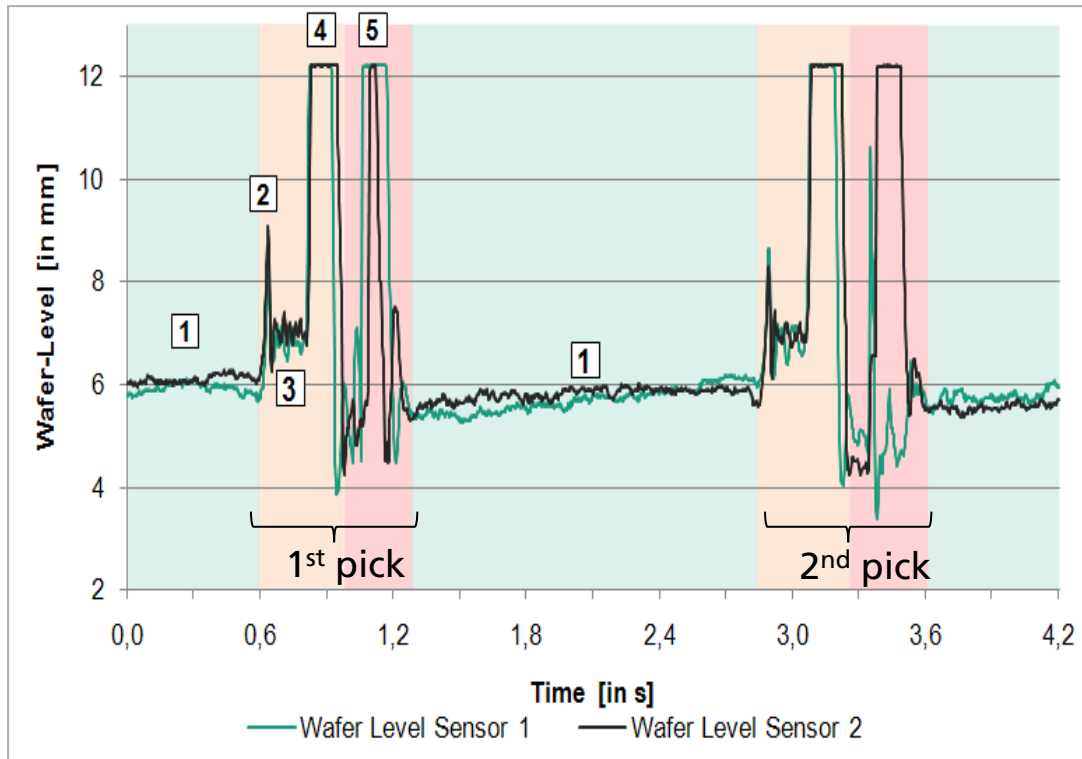
**1. Precise Pre-Separation**

**2. Save Gripping Process (repetition)**



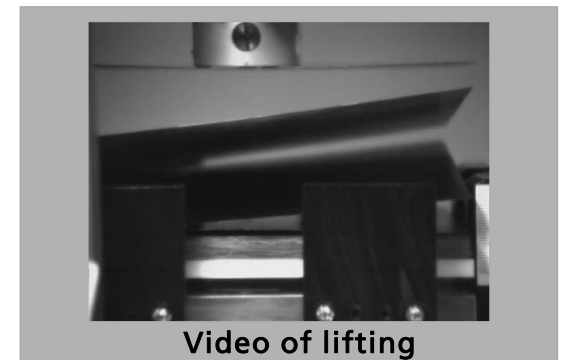
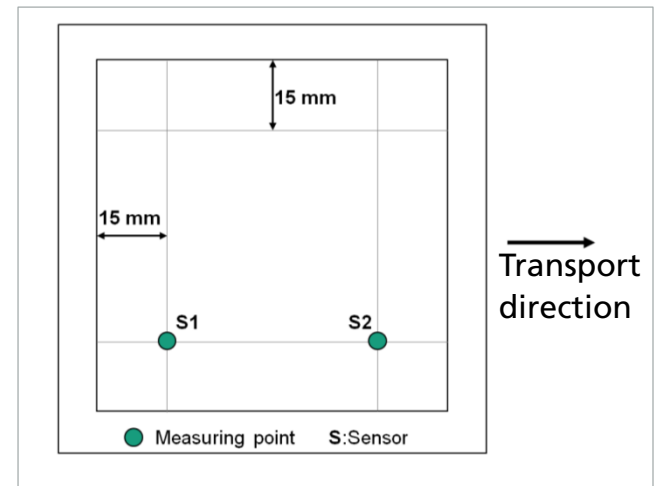
# Wafer behavior after gripping (2 sensors)

Wafer-Level



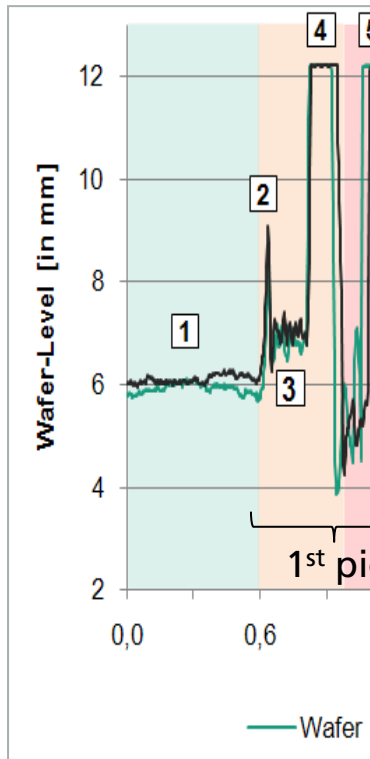
- |                  |                 |  |
|------------------|-----------------|--|
| 1 Pre-Separation | 3 Waiting       | 5 Lifted 2 <sup>nd</sup> topmost wafer |
| 2 Picking        | 4 Transport (z) |  |

Sensor Positions

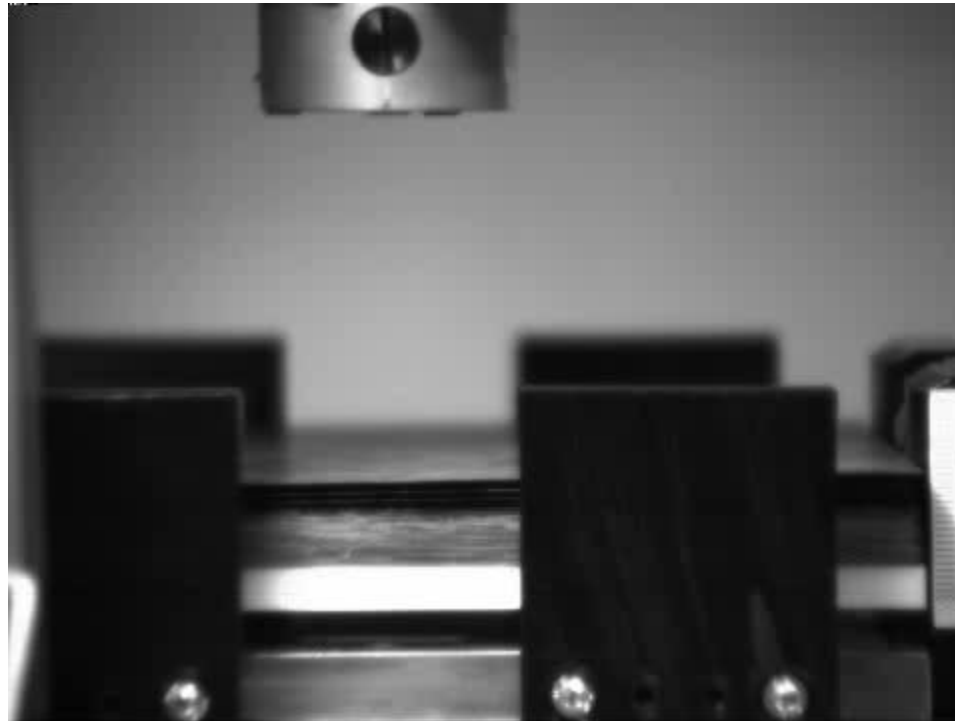




# Wafer behavior after gripping (2 sensors)



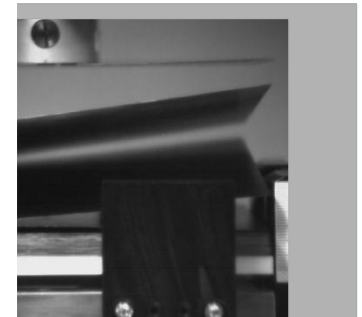
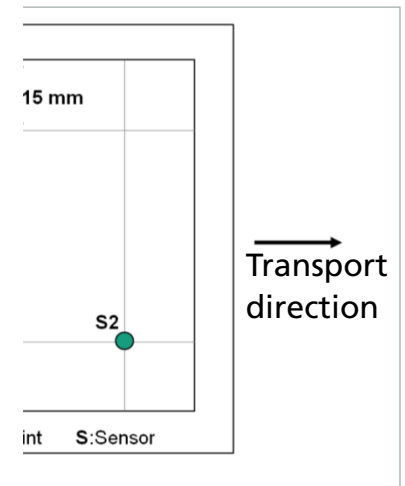
- 1 Pre-Separation
- 2 Picking



12.10.2010 10:55:50 1900 0635,4[ms] 480x360, 2989 Hz, 60  $\mu$ s, \*2,  
MotionBLITZ Cube3 #00163, V1.9.21

- 4 Transport (z)

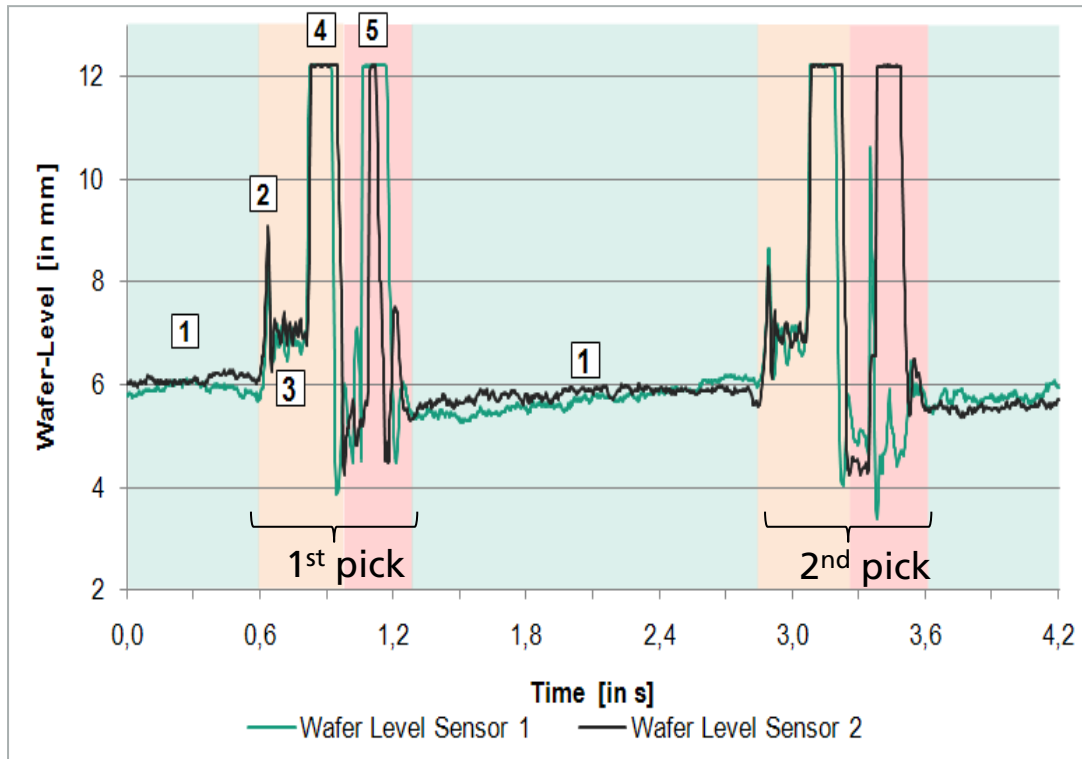
or Positions



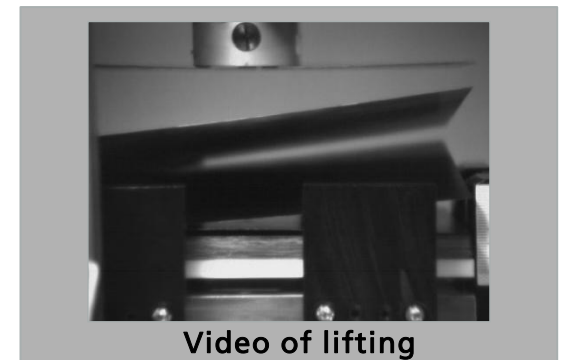
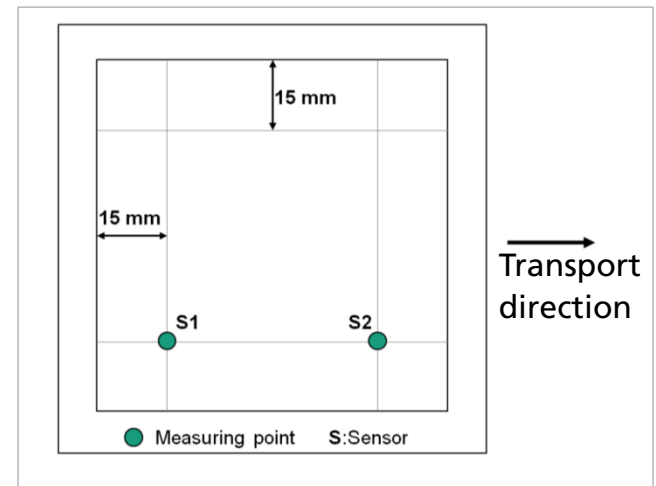
video of lifting

# Wafer behavior after gripping (2 sensors)

Wafer-Level



Sensor Positions



- |                  |                 |  |
|------------------|-----------------|--|
| 1 Pre-Separation | 3 Waiting       | 5 Lifted 2 <sup>nd</sup> topmost wafer |
| 2 Picking        | 4 Transport (z) |  |

# Target values and factors of interest

<b><i>Target Values</i></b>	<b><i>Factors to be investigated</i></b>	
<b>1. Vibrations</b>	<b>1. Number of nozzles</b>	
<b>2. Cycle time</b>	<b>2. Nozzle configuration</b>	
<b>3. Operating costs (compressed air)</b>	<b>3. Nozzle slot shape</b>	
<b>4. Wafer stress</b>	<b>4. Pressure</b>	
	<b>5. Nozzle direction</b>	
	<b>6. Distance nozzle-wafer</b>	
	<b>7. Position gripper-wafer for pick-process</b>	
	<b>8. Different wafer thicknesses</b>	
	<b>9. Shape of side walls</b>	

# 1<sup>st</sup> step: Pre-separation

Control Factor	# Types	Specification				
#Nozzle	4	1	2	3	4	
<b>Nozzle Position</b>						
1 Nozzle	2					
		1.1	1.2			
2 Nozzles	6					
		2.1	2.2	2.3	2.4	
		2.5	2.6			
3 Nozzles	10					
		3.1	3.2	3.3	3.4	3.5
		3.6	3.7	3.8	3.9	3.10
4 Nozzles	12					
		4.1	4.2	4.2	4.4	
		4.5	4.6	4.7		
		4.8	4.9	4.10	4.11	4.12
Slot	4		—	+	×	
Pressure [bar]	3	≤0,7	1,0	≥1,3		
Nozzle direction	3	→	↗	↘		
Distance N-W	3	~0	5	10		

Pretests

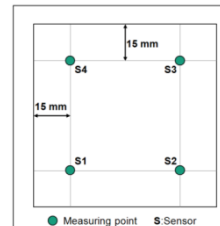
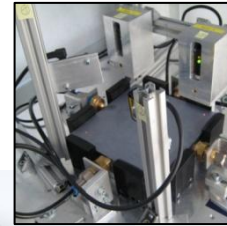
Control Factor	# resulting Types	Specification				
#Nozzles	2	<del>1</del>	2	<del>3</del>	4	
<b>Nozzle Position</b>						
2 Nozzles	2		<del></del>	<del></del>	<del></del>	
		2.1	2.2	2.3	2.4	
		<del></del>				
		2.5	2.6			
4 Nozzles	3		<del></del>	<del></del>	<del></del>	
		4.1	4.2	4.2	4.4	
			<del></del>	<del></del>		
		4.5	4.6	4.7		
		<del></del>	<del></del>	<del></del>		<del></del>
		4.8	4.9	4.10	4.11	4.12
Slot	4		—	+	×	
Pressure [bar]	2	≤0,7	1,0	<del>≥1,3</del>		
Nozzle direction	2	→	<del>↗</del>	<del>↘</del>		
Distance N-W	1	~0	<del>5</del>	<del>10</del>		

First Results: Separation possible with these settings  
 Next Step: Determination of factors with main significance

## 2. Creation of Screening design

Nr.	Position	Slot	Pressure	Nozzle-Direction	Safety Factor
1	1	1	1	1	1
2	1	2	2	2	2
3	1	3	3	3	3
4	1	4	4	4	4
5	2	1	2	3	4
6	2	2	1	4	3
7	2	3	4	1	2
8	2	4	3	2	1
9	3	1	3	4	2
10	3	2	4	3	1
11	3	3	1	2	4
12	3	4	2	1	3
13	4	1	4	2	3
14	4	2	3	1	4
15	4	3	2	4	1
16	4	4	1	3	2

## 3. Realization of Experiments for 120µm & 200µm wafer



## 1. Determination of quantitative + qualitative factors with 4 levels

Control Factor	Factor Level			
	1	2	3	4
Nozzle Position				
Slot	1.1	1.2	4.1	4.5
Pressure [bar]	0.3	0.5	0.7	1.0
Nozzle Direction	0°	-5°	-10°	+5°

Determination of suitable settings

## 4. Analysis of Variance Determination of significant factors

	120			200			
	Diff	Sig <sup>1</sup>	SD <sup>2</sup>	Sig <sup>1</sup>	Diff	Sig <sup>1</sup>	SD <sup>2</sup>
Position	2,895	-	2,582	-	3,455	-	5,131
Slot	8,050	**	6,249	*	4,957	*	4,560
Pressure	0,430	-	0,358	-	1,366	-	1,365
Nozzle Direction	1,473	-	1,130	-	1,928	-	1,823

<sup>1</sup> Significance, <sup>2</sup> Standard Deviation

## 5. Determination of suitable factors for pre-separation

Control Factor	Factor Level			
	1	2	3	4
Nozzle Position				
Slot	1.1	1.2	4.1	4.5
Pressure [bar]	0,3 <sup>1</sup>	0,5 <sup>2</sup>	0,7	1,0
Nozzle Direction	0°	-5°	-10°	+5°

<sup>1</sup> 120 µm, <sup>2</sup> 200 µm

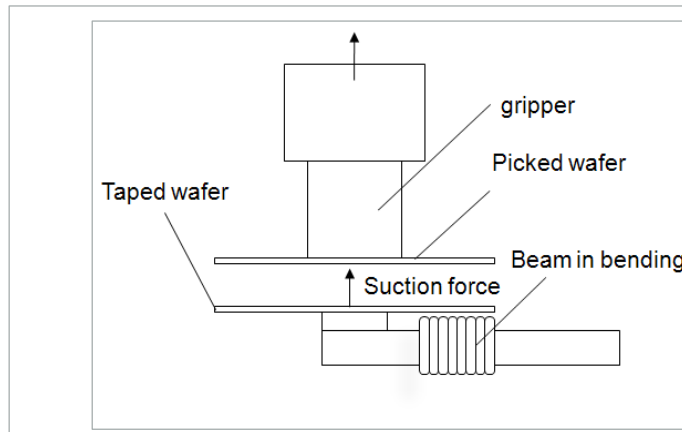
## 2<sup>nd</sup> step: picking process

### 1. Significance of the suction force

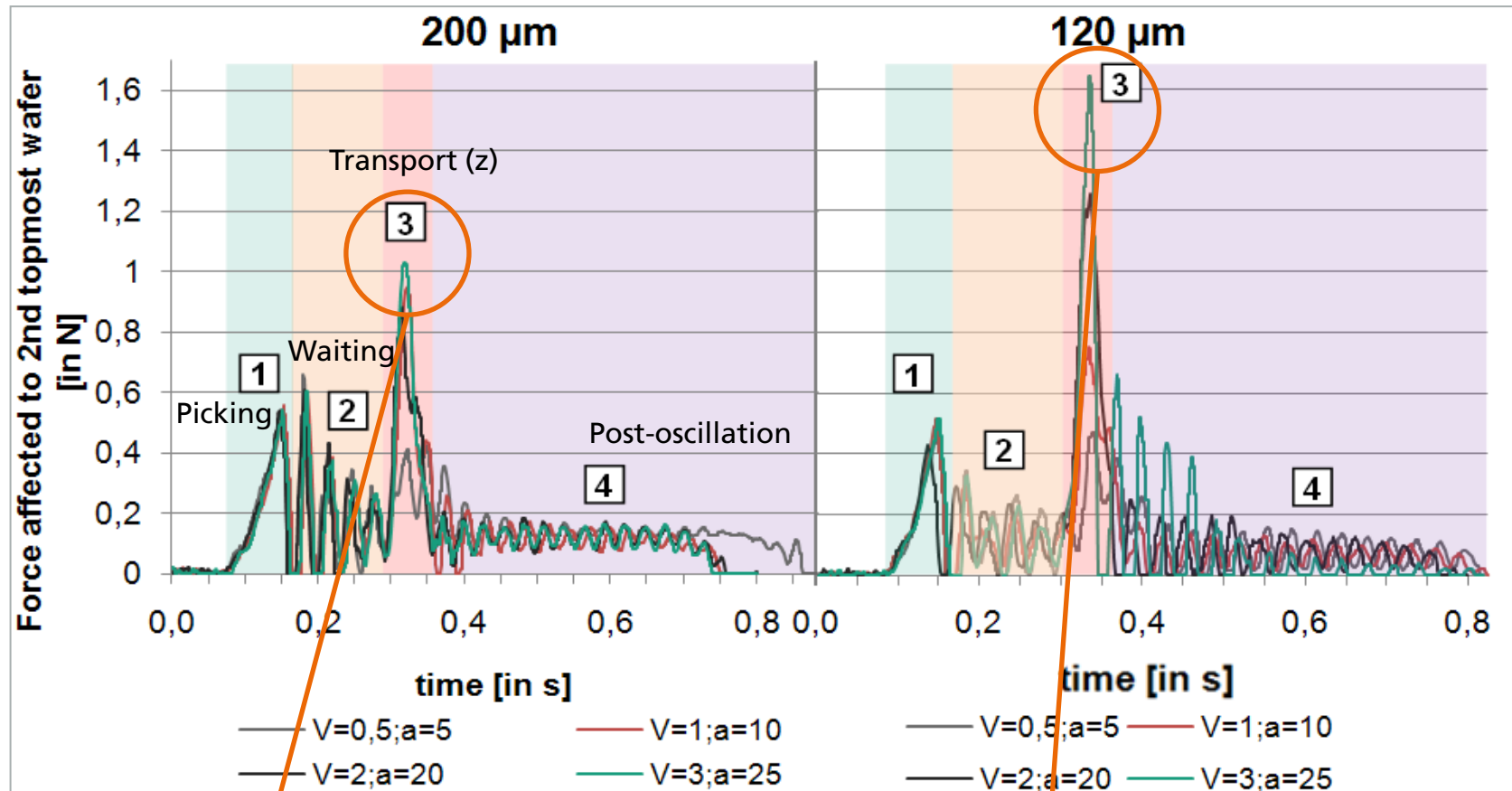
#### ■ Wafer-weight:

	Wafer-weight depending on wafer-thickness (in N)	
	120	200
Multi	0,069	0,111
Mono	0,053	0,124

#### ■ Measuring with beam in bending (0-20N):



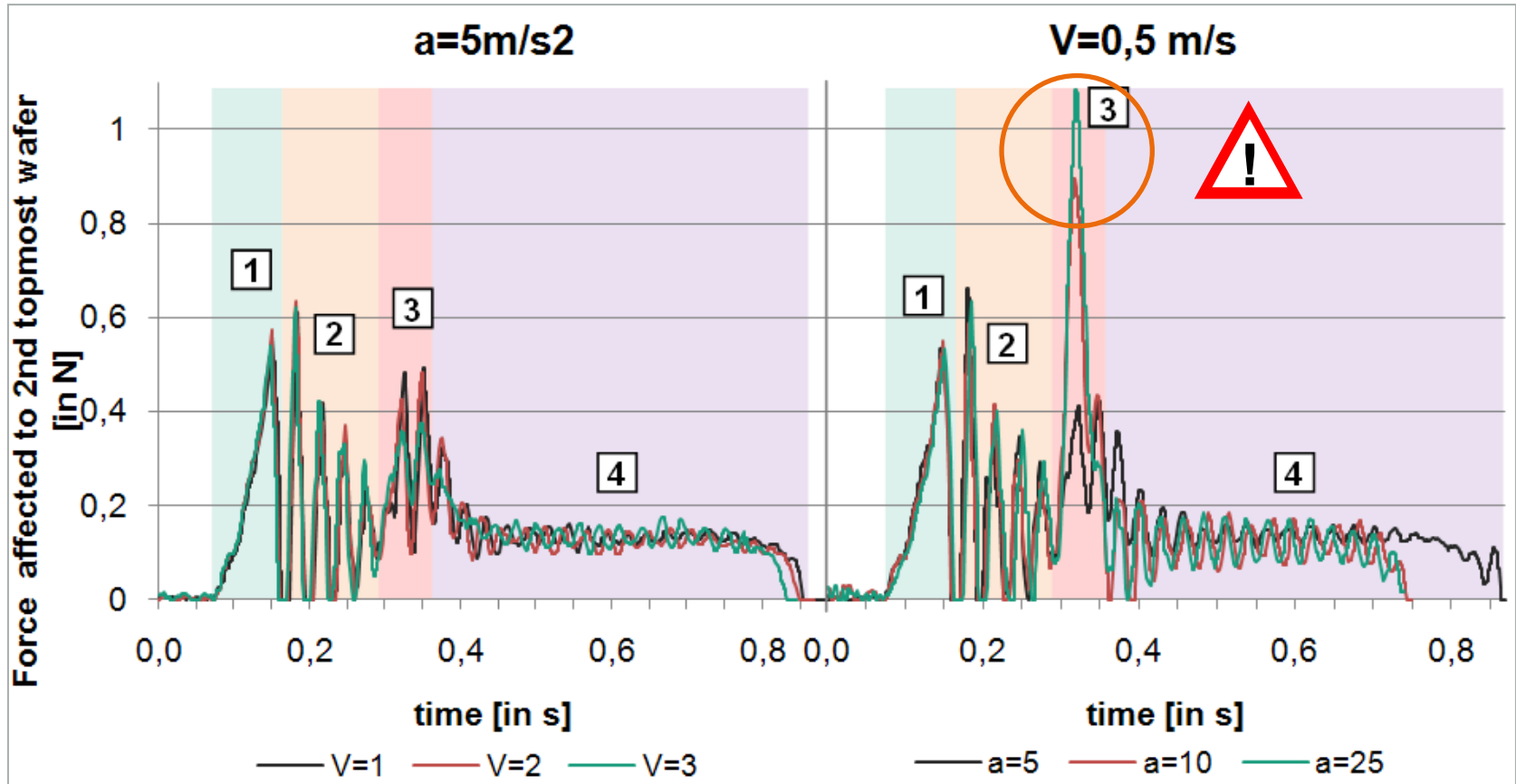
# Affected force depending on wafer-thickness



Force **~10** times wafer weight  
(200 μm  $\cong$  0,111N)

Force **~25** times wafer weight  
(120 μm  $\cong$  0,069N)

# Affected force depending on picking acceleration (a) and velocity (V)

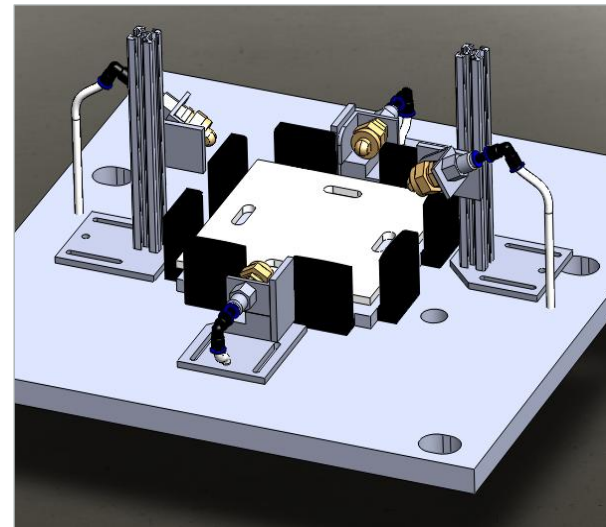
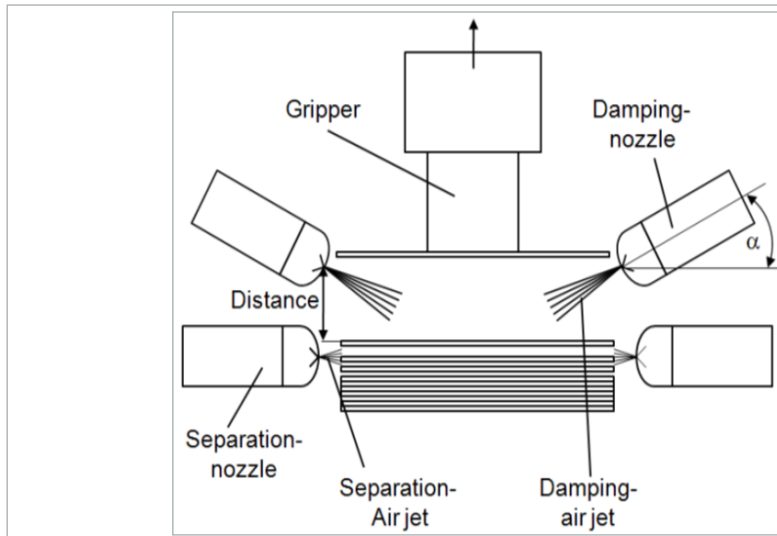


➡ No visible effect of velocity

➡ Crucial factor acceleration



## 2. Air jet damping



- Vibration damping starts at certain pressure
- No picking possible when air pressure is too high

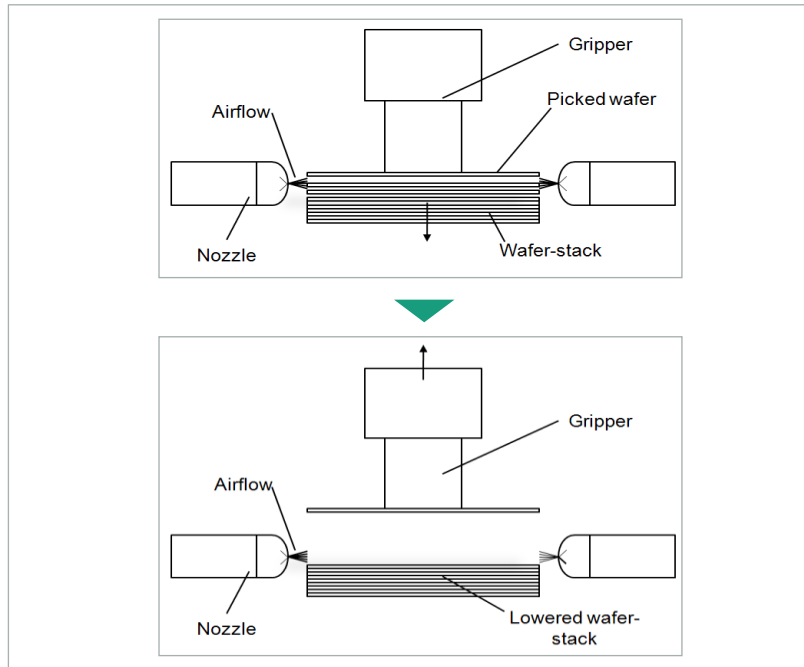
+	-
• Improvement of process	• Extra load on wafer • 120 $\mu\text{m}$ less impact



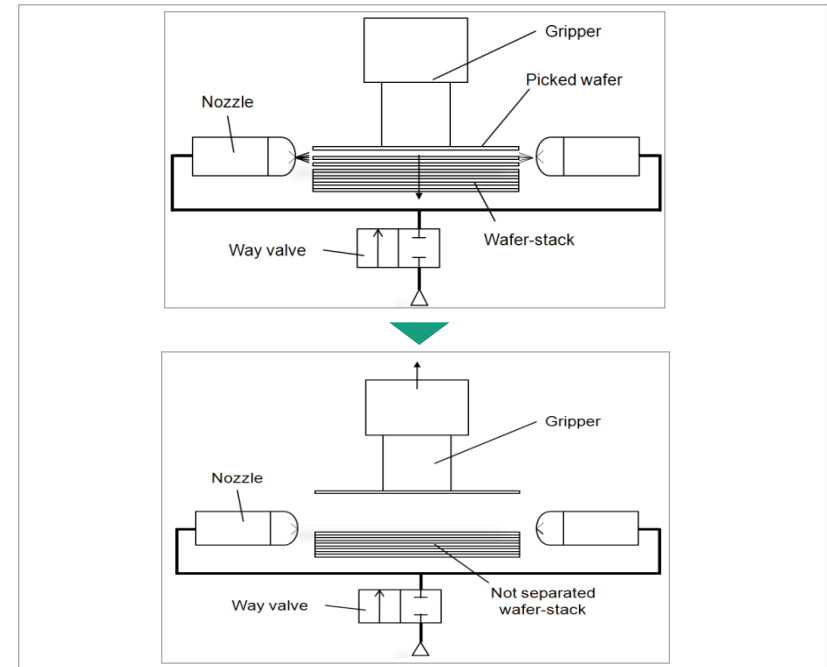
Only as add-on

### 3. Stack lowering

➔ Goal: Reduction of suction force



### 4. Pulsation of separation airflow



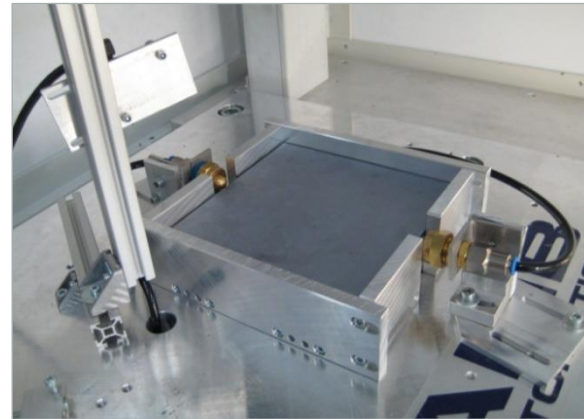
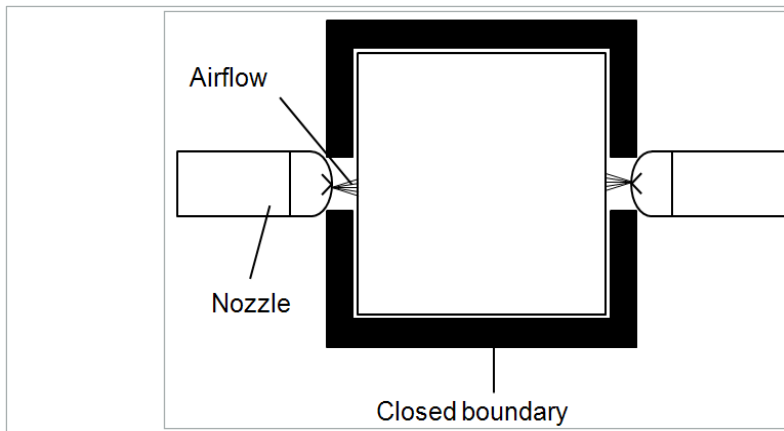
	Incorrect picking* depending on wafer-thickness (in %)		
	200 µm	180 µm	120 µm
Without stack lowering/ pulsation	15	20	26
With stack lowering	1	7	13
With pulsation	0	0	10

\* Picking with maximal parameters:  $V=3\text{m/s}$ ;  $a,d= 25\text{m/s}^2$

- ➔
- Pulsation achieves better results
  - Critical wafer-thickness 120 µm

## 5. Closed side wall design

- ➡ Goals:
- Research on consequences to picking process
  - Reduction of air needed for pre-separation



- Picking not possible due to evacuated space under topmost wafer
- No improvement in pre-separation process

➡ **Not suitable**

# 5. Summary and Outlook

## Pre-separation:

- Analysis and determination of significant factors
- Specification of suitable settings for reliable pre-separation

## Picking process:

- Characterization of suction force and influencing factors
- Investigation on methods for reliable separation process

## Outlook:

- New nozzle type (e.g. flat jet)
- Damping with alternative medium (e.g. ultrasonic sound)